

XA-7889A Re
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

Kenji NISHI

Appln. No.: 08/994,758

Group Art Unit: 2851

Filed: December 19, 1997

Examiner: A. Mathews

For: PROJECTION EXPOSURE APPARATUS



9/18
Slayge
8/4/99

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

RECEIVED
JUL 28 1999
TC 2800 MAIL ROOM

Sir:

In response to the Office Action mailed January 25, 1999, please amend the above-identified patent application as indicated below.

IN THE CLAIMS:

1 9. (Amended) A scanning exposure apparatus
2 comprising:
3
4 a scanning system for synchronously scanning a mask and
5 a photosensitive substrate at respective speeds which are
6 different from each other for scanning exposure; and
7 an adjusting system for moving the mask to decrease a
8 positional deviation between the mask and the substrate,
9 independently of scanning of the mask which is performed by
 said scanning system, during the scanning exposure.

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